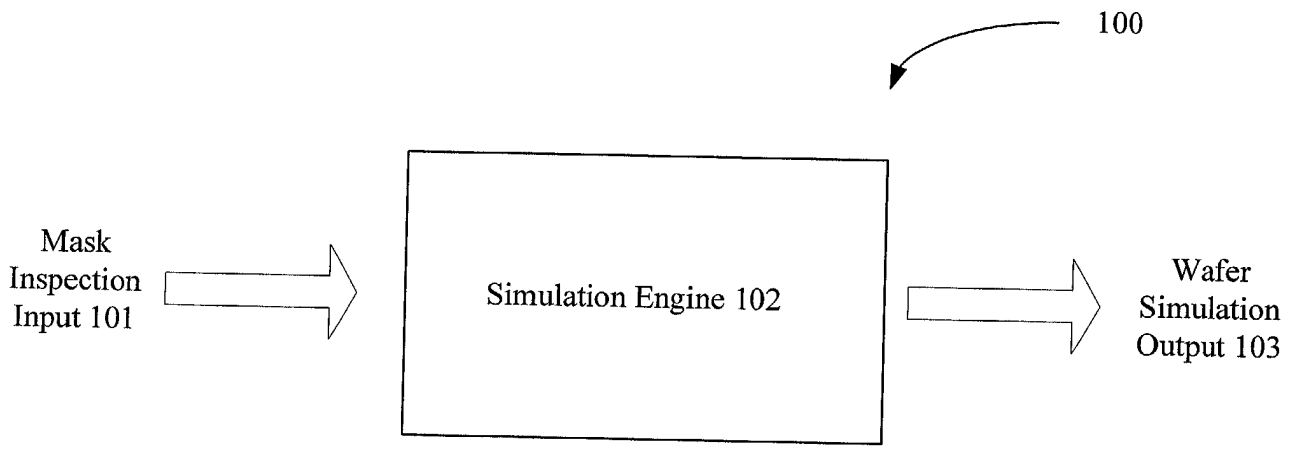
100
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Inspection
Input 101
Simulation Engine 102
Wafer
Simulation
Output 103

Figure 1

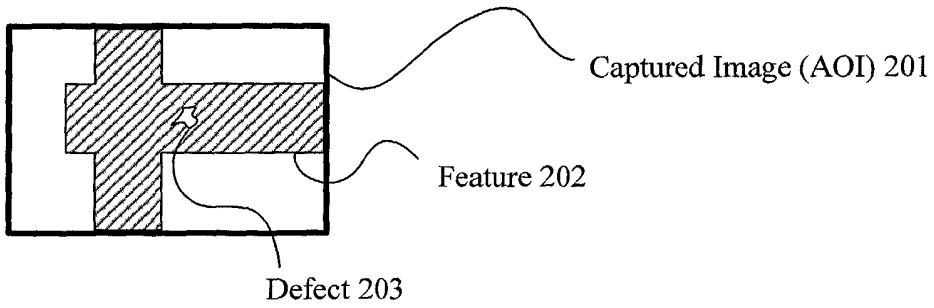


Figure 2A

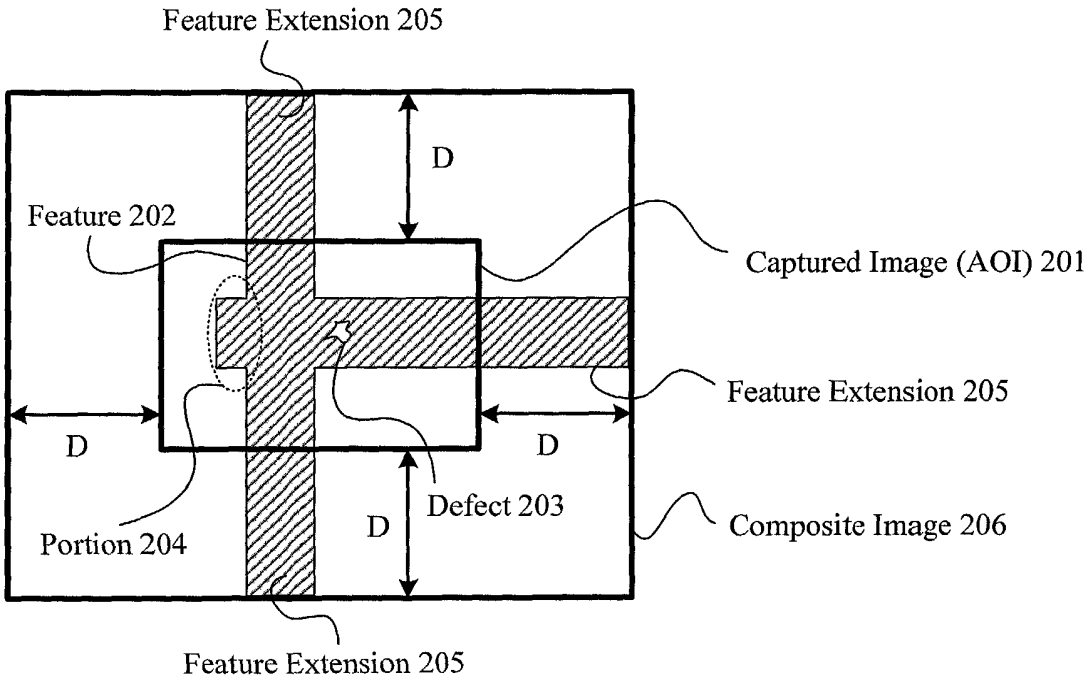


Figure 2B

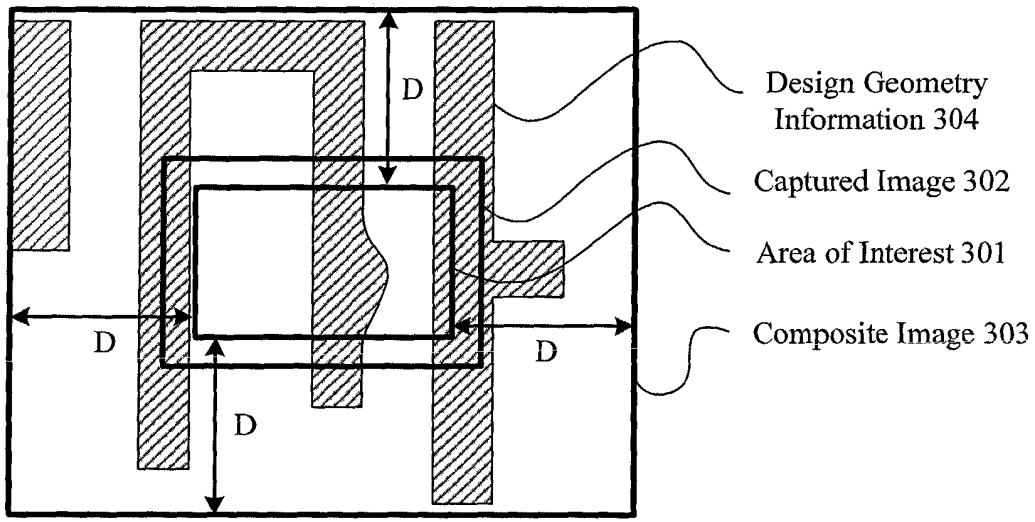


Figure 3A

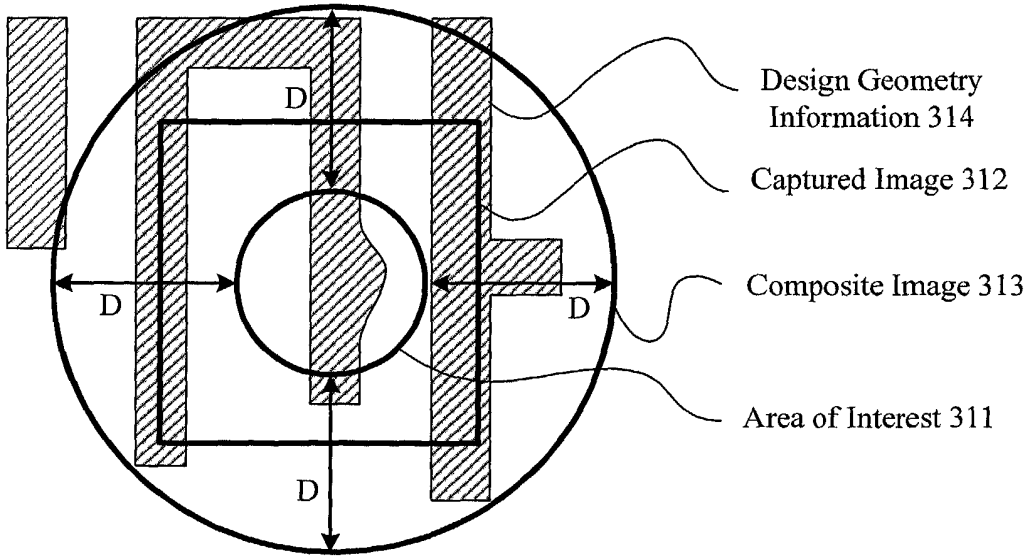


Figure 3B

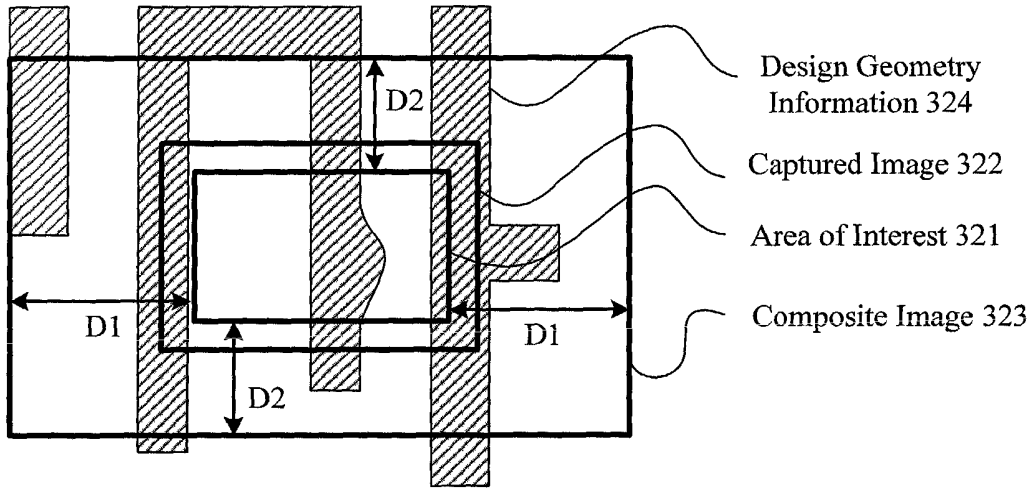


Figure 3C

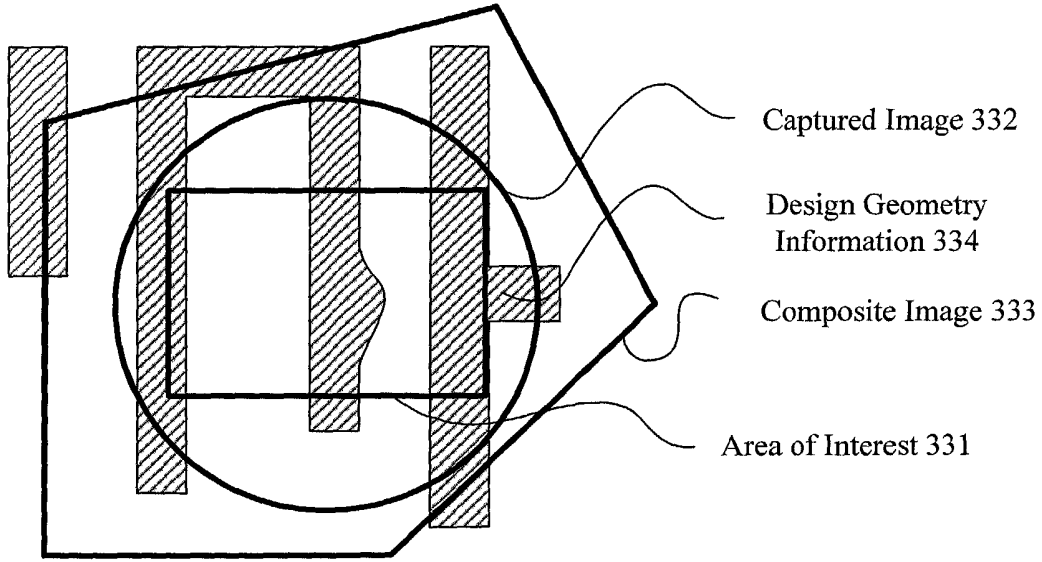
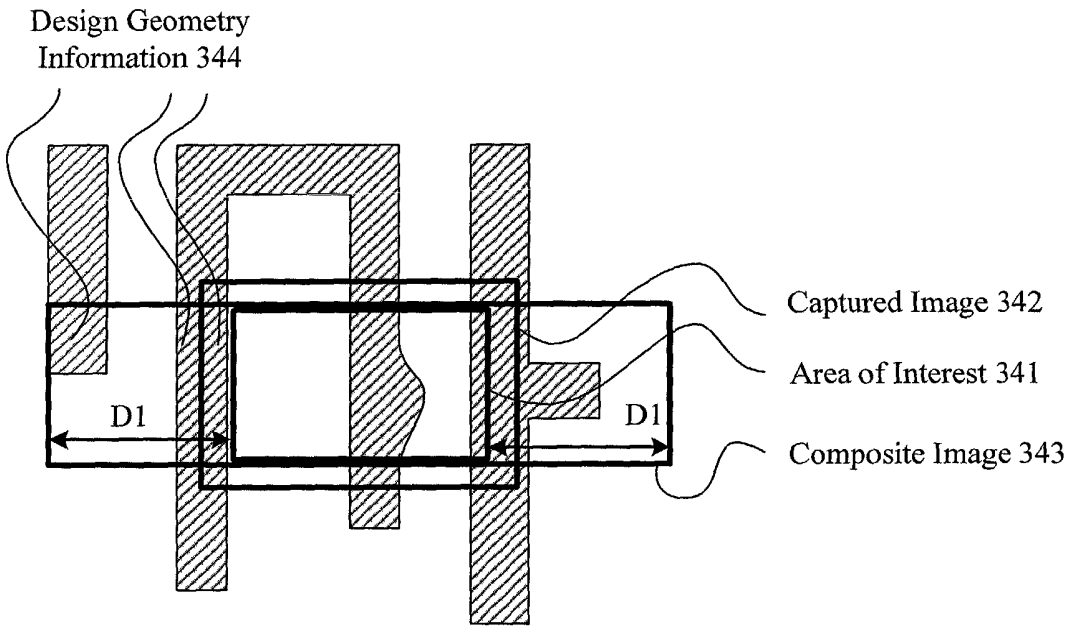


Figure 3D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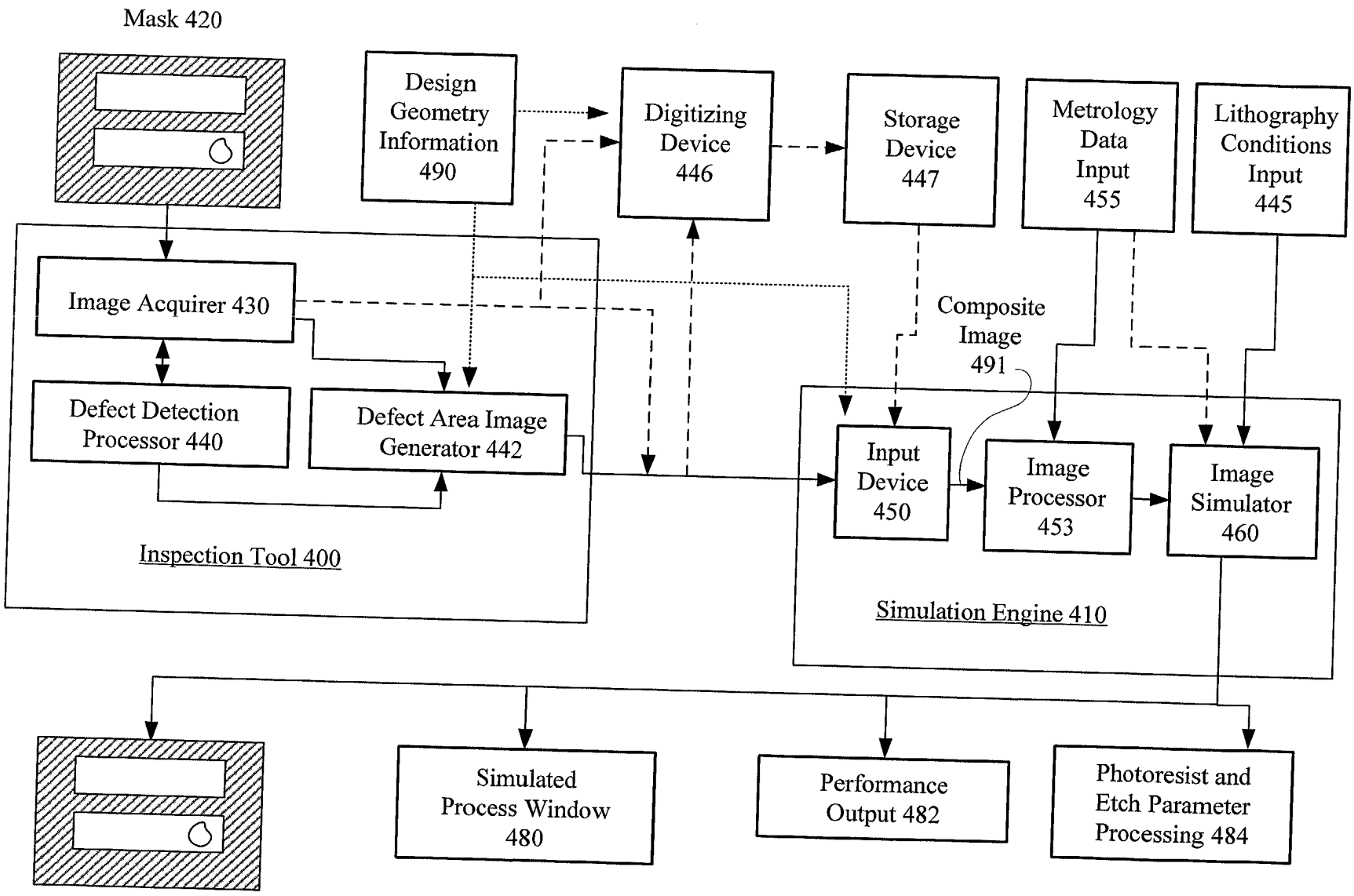
Captured Image 342
Area of Interest 341
Composite Image 343
D1
D1

Figure 3E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Storage Device 447
Metrology Data Input 455
Lithography Conditions Input 445
Image Acquirer 430
Composite Image 491
Defect Detection Processor 440
Defect Area Image Generator 442
Input Device 450
Image Processor 453
Image Simulator 460
Inspection Tool 400
Simulation Engine 410
Simulated Process Window 480
Performance Output 482
Photoresist and Etch Parameter Processing 484
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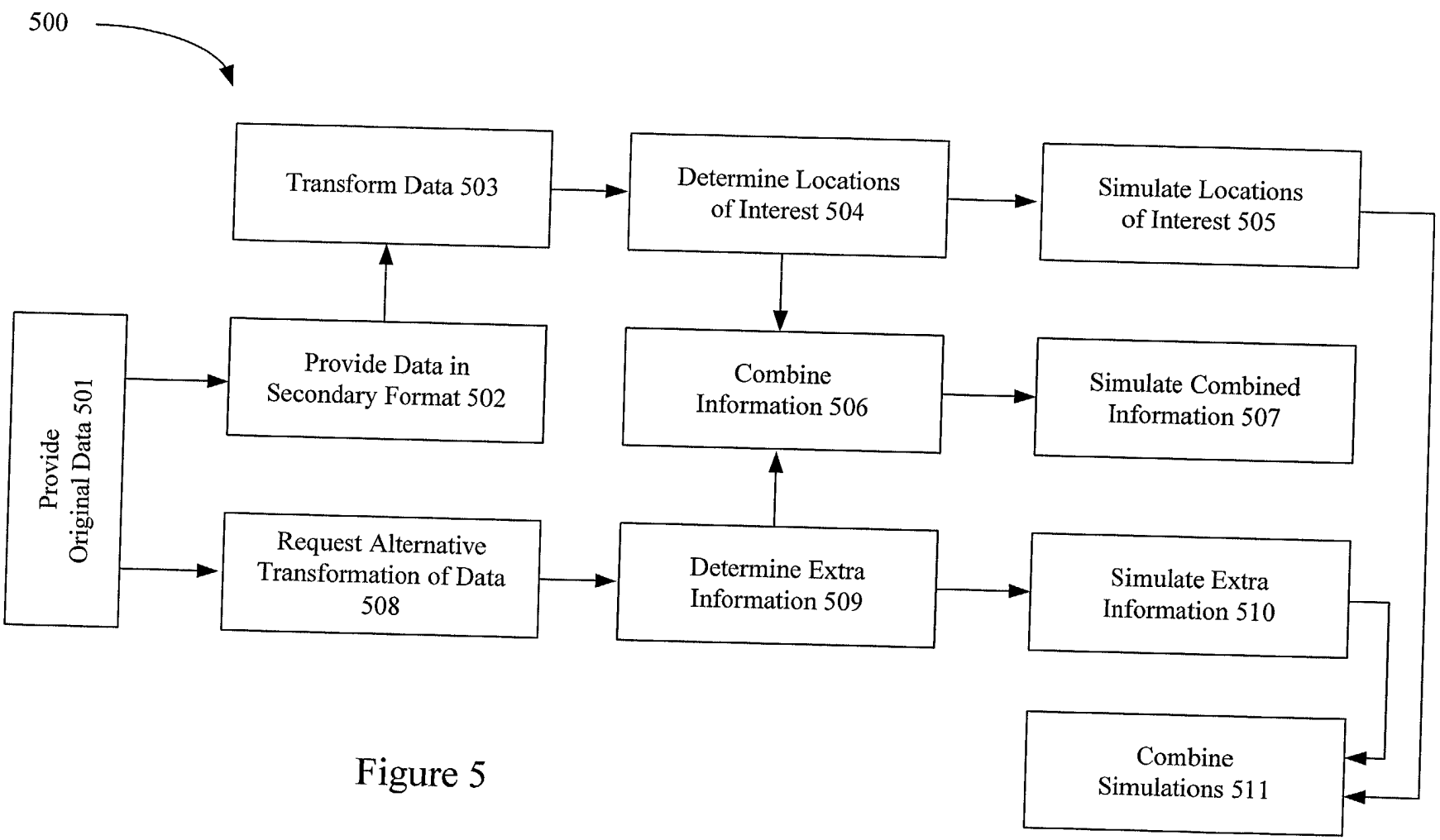
Figure 4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Provide Data in Secondary Format 502
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Figure 5

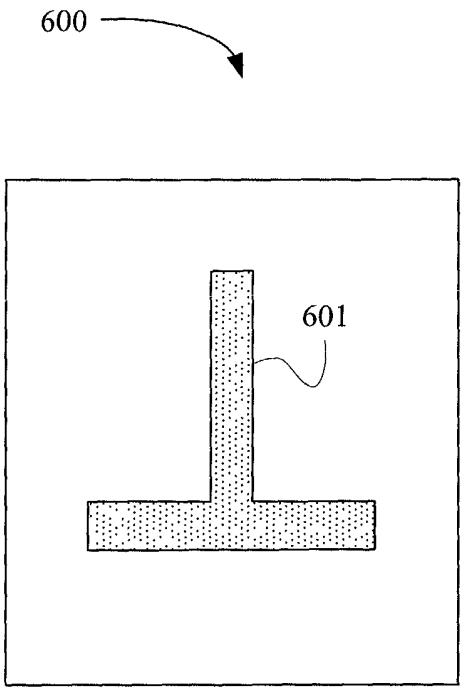

Figure 6A

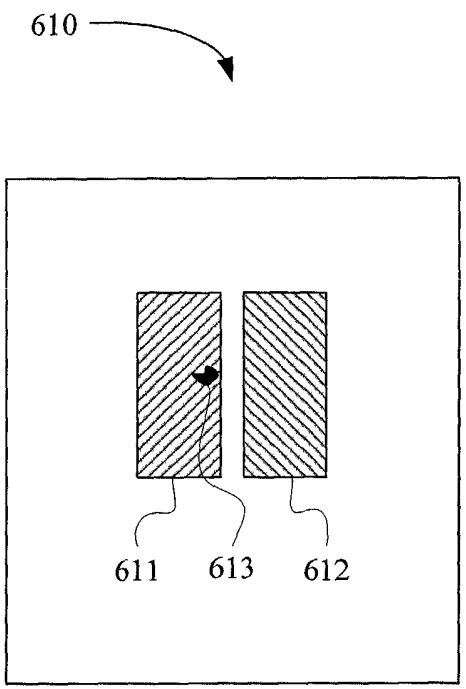

Figure 6B

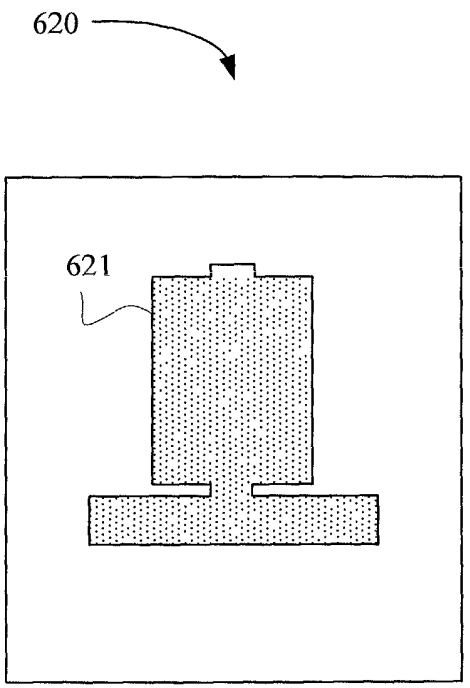

Figure 6C